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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Satoshi Watanabe et al.

Examiner: V. Perez-Ramos

Serial No.: 09/401,490

Group Art Unit: 1765

Filed: September 22, 1999

Title: RESIST COMPOSITION AND PATTERNING METHOD

**RESPONSE TO RESTRICTION REQUIREMENT**

Assistant Commissioner for Patents  
Washington, D.C. 20231


RECEIVED  
JUL 16 2002  
TECHNOLOGY CENTER 1100

Sir:

In response to the Restriction Requirement dated June 10, 2002, Applicant's hereby elect with traverse Group I drawn to positive working photoresists. Applicants elect as a single species Resist Composition A. The fluorochemical surfactants of this invention find use in both positive and negative photoresists. It has not been shown why it would be an undue burden to search and examine resists with fluorochemical surfactants without regard as to whether the resists are positive or negative working resists. It is also not clear how restricting the search and examination to positive or negative resists with these fluorochemical surfactants would relieve any undue burden since it has not been shown that the field of search will vary with this election.

No fee is believed to be due with this response, however, the Commissioner is hereby authorized to charge any fees associated with this response or credit any overpayment to Deposit Account No. 13-3402.

Respectfully submitted,

  
James E. Ruland (Reg. No. 37,432)  
Attorney/Agent for Applicant(s)

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Attorney Docket No.: KOJIM 289

Date: July 10, 2002

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